

IN THE CLAIMS

Please cancel claims 3 and 10, without prejudice or disclaimer.

Please amend claims 1 and 7 as follows:

1. **(Currently Amended)** A method for forming a first-property semiconductor film at a desired position on a substrate, comprising the steps of:

- a) preparing the substrate having a second-property semiconductor film formed ~~thereon, wherein the substrate has an alignment mark previously formed thereon;~~
- b) preparing an optical mask having a predetermined pattern on another substrate which is apart from the substrate;
- c) relatively positioning a projection area of the optical mask at the desired position on the substrate ~~by using the alignment mark as a reference;~~
- d) irradiating the desired position of the second-property semiconductor film with laser light through the optical mask to change an irradiated portion of the second-property semiconductor film to the first-property semiconductor film; and
- e) forming an insulation film on the first-property semiconductor film and the second-property semiconductor ~~film. film;~~
wherein the optical mask has an alignment mark pattern, wherein, in the step (d), an alignment mark corresponding to the alignment mark pattern is formed solely by irradiation, and wherein the alignment mark is visible due to a difference in optical characteristic between the first-property semiconductor film and the second-property semiconductor film.

2.-3. (Canceled).

4. **(Currently Amended)** The method according to claim 3, 1, wherein a positioning process after the step (d) is performed with reference to the alignment mark.

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5. (Canceled).**

6. **(Currently Amended)** The method according to claim 3, 1, wherein the first-property semiconductor film is a crystalline semiconductor film and the second-property semiconductor film is an amorphous semiconductor film.

7. **(Currently Amended)** A method for forming a crystalline semiconductor film at a desired position on a substrate, comprising the steps of:

- a) preparing the substrate having an amorphous semiconductor film formed ~~thereon~~,
~~wherein the substrate has an alignment mark previously formed thereon~~;
- b) preparing an optical mask having a predetermined pattern on another substrate which is apart from the substrate;
- c) relatively positioning a projection area of the optical mask at the desired position on the substrate ~~by using the alignment mark as a reference~~;
- d) irradiating the desired position of the amorphous semiconductor film with laser light through the optical mask to change an irradiated portion of the amorphous semiconductor film to the crystalline semiconductor film; and

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- e) forming an insulation film on the crystalline semiconductor film and the amorphous semiconductor film: film;

wherein the optical mask has an alignment mark pattern, wherein, in the step (d), an alignment mark corresponding to the alignment mark pattern is formed solely by irradiation, and wherein the alignment mark is visible due to a difference in optical characteristic between the first-property semiconductor film and the second-property semiconductor film.

- 8. (Original) The method according to claim 7, further comprising the step of:
 - (f) forming an island comprised of the insulation film and the crystalline semiconductor film by a patterning process, wherein the crystalline semiconductor film of the island is a single-crystal semiconductor film used for source, drain, and channel regions of a field effect transistor.

9.-10. (Canceled).

11.-14. (Withdrawn).
